



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Huey-Chiang Liou et al.	§	Group Art Unit:	2823
		§		
Serial No.:	10/695,103	§		
		§	Examiner:	Trung Q. Dang
Filed:	October 28, 2003	§		
		§		
For:	Langmuir-Blodgett Chemically Amplified Photoresist	§	Atty. Dkt. No.:	ITL.1054US (P17790)
		§		
Customer No.:	21906	§	Confirmation No.:	4735

Mail Stop-Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

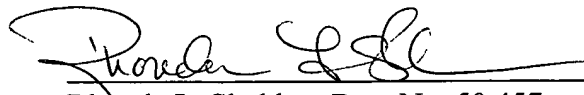
Dear Sir:

Applicant submits the references listed on the attached form PTO 1449 together with any required copies of such references.

This statement is being filed after a first Office action on the merits, but before receipt of a final Office action, a Notice of Allowance or an action that otherwise closes prosecution in the application. A check for \$180 in payment of the late submission fee of §1.17(p) is enclosed. Please apply any additional charges or credits to Deposit Account No. 20-1504(ITL.1054US).

Respectfully submitted,

Date: October 26, 2004

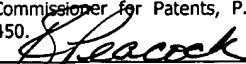
  
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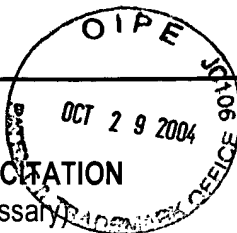
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Date of Deposit: October 26, 2004  
I hereby certify under 37 CFR 1.8(a) that this correspondence is being deposited with the United States Postal Service as **first class mail** with sufficient postage on the date indicated above and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.  


**INFORMATION DISCLOSURE CITATION**

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ATTY DOCKET NO.

ITL 1054US(P17790)

SERIAL NO.

10/695,103

APPLICANT(S):

Huey-Chiang Liou et al.

FILING DATE:

October 28, 2003

GROUP ART UNIT:

2823

**U.S. PATENT DOCUMENTS**

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
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**FOREIGN PATENT DOCUMENTS**

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	AJ							
	AK							
	AL							
	AM							
	AN							
	AO							
	AP							

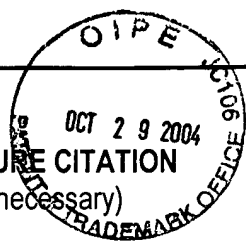
**OTHER DOCUMENTS** (Including Author, Title, Date, Pertinent Pages, Etc.)

	AQ	S. Elhadj, J. W. Woody, V. S. Niu and R. F. Saraf, <i>Orientation of self-assembled block copolymer cylinders perpendicular to electric field in mesoscale film</i> , Applied Physics Letters, vol. 82, no. 6, 10 Feb. 2003, p. 871-3.
	AR	Huiwen Liu, Bharat Bhushan, <i>Orientation and relocation of biphenyl thiol self-assembled monolayers under sliding</i> , Ultramicroscopy, vol. 91, no. 1-4, May 2002, p. 177-83.
	AS	Sang Jung Ahn, Yun Kyeong Jang, Haeseong Lee, and Haiwon Lee, <i>Mechanism of atomic force microscopy anodization lithography on a mixed Langmuir-Blodgett resist of palmitic acid and hexadecylamine on silicon</i> , Applied Physics Letters, vol. 80, no. 14, 8 April 2002, p. 2592-4.
	AT	Tiesheng Li, Masaya Mitsuishi, and Tokuji Miyashita, <i>Photodegradable polymer LB films for nano-lithographic imaging techniques</i> , Thin Solid Films, vol. 389, no. 1-2, 15 June 2001, p. 267-71.

EXAMINE

DATE CONSIDERED

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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2823**OTHER DOCUMENTS** (Including Author, Title, Date, Pertinent Pages, Etc.)

BA	N.G. Semaltianos, H. Araujo, and E.G. Wilson, <i>Polymerization of Langmuir-Blodgett films of diacetylenes</i> , Surface Science, vol. 460, no. 1-3, 20 July 2000, p. 182-9.
BB	Hiroyuki Sugimura, Atsushi Hozumi and Osamu Takai, <i>Fabrication of Coplanar Microstructures Composed of Multiple Organosilane Self-Assembled Monolayers</i> , IEICE Transactions on Electronics, vol. E83-C, no. 7, July 2000, p. 1099-103.
BC	M. Sundermann, J. Hartwich, K. Rott, D. Meyners, E. Majkova, U. Kleineberg, M. Grunze, U. Heinzmann, <i>Nanopatterning of Au absorber films on Mo/Si EUV multilayer mirrors by STM lithography in self-assembled monolayers</i> , Surface Science, vol. 454-456, 20 May 2000, p. 1104-9.
BD	Richard D. Peters, Xiao M. Yang, Tae K. Kim, B. H. Sohn, and Paul F. Nealey, <i>Using Self-Assembled Monolayers Exposed to X-rays To Control the Wetting Behavior of Thin Films of Diblock Copolymers</i> , Langmuir, vol. 16, no. 10, 16 May 2000, p. 4625-31.
BE	Hiroyuki Sugimura, Kazuya Ushiyama, Atsushi Hozumi, and Osamu Takai, <i>Micropatterning of Alkyl- and Fluoroalkylsilane Self-Assembled Monolayers Using Vacuum Ultraviolet Light</i> , Langmuir, vol. 16, no. 3, 8 Feb. 2000, p. 885-8.
BF	Hiroyuki Maruyama, Nobuyuki Kosai, Tadatake Sato, Shigehito Sagisaka, Hiroshi Segawa, Takeo Shimidzu and Kazuyoshi Tanaka, <i>Nanometer-Scale Lithography on the Oligosilane Langmuir-Blodgett Film</i> , Japanese Journal of Applied Physics, Part 1, vol. 36, no. 12A, Dec. 1997, p. 7312-16.
BG	Chang Nam Kim, Dong Woo Kang, Eung Ryul Kim, and Haiwon Lee, <i>Fabrication of a Polymethylphenylmethacrylate Resist by Using Electron Beam Lithography</i> , Journal of the Korean Physical Society, vol. 31, no. 1, July 1997, p. 154-7.
BH	T. Sato, and H. Ahmed, <i>Observation of a Coulomb staircase in electron transport through a molecularly linked chain of gold colloidal particles</i> , Applied Physics Letters, vol. 70, no. 20, 19 May 1997, p. 2759-61.
BI	Earl T. Ada, Luke Hanley, Sergei Etchin, John Melngailis, Walter J. Dressick, Mu-San Chen and Jeffrey M. Calvert, <i>Ion beam modification and patterning of organosilane self-assembled monolayers</i> , Journal of Vacuum Science & Technology B, vol. 13, no. 6, Nov.-Dec. 1995, p. 2189-96.
BJ	
BK	
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